The listing of claims will replace all prior versions and listings of claims in the application:

LISTING OF CLAIMS:

Claims 1-17 (withdrawn)

18. (currently amended) A component for use in forming a printed wiring board, comprising:

a metal carrier substrate;

a separation facilitating layer formed on the metal carrier substrate;

a vapor-deposited layer of copper on the separation facilitating layer, wherein the vapor-deposited layer <u>has a thickness in a range of 50Å to 10,000Å to protect[[s]]</u> the separation facilitating layer; and

an electrodeposited layer of copper having a thickness in a range of 1 μm to 35 μm on the vapor-deposited layer of copper.

- 19. (original) A component according to claim 18, wherein said separation facilitating layer includes at least one metal oxide.
- 20. (original) A component according to claim 19, wherein said metal oxide is selected from the group consisting of: aluminum oxide, tin oxide, chromium oxide, nickel oxide, copper oxide, an oxide of stainless steel and zinc oxide.
- 21. (original) A component according to claim 18, wherein said separation facilitating layer includes at least one organic material.
- 22. (original) A component according to claim 21, wherein said separation facilitating layer includes at least one organic material selected from the group consisting of: silane, benzotriazole (BTA), and isopropyl alcohol.

- 23. (currently amended) A component according to claim 18, wherein said separation facilitating layer has a thickness in a range of 5Å to 1,000Å.
- 24. (currently amended) A component according to claim 18, wherein said <u>metal</u> carrier substrate is comprised of copper.
- 25. **(original)** A component according to claim 24, wherein said separation facilitating layer is a stabilization layer.
- 26. (original) A component according to claim 25, wherein said stabilization layer includes chromium oxide and zinc oxide.
- 27. (currently amended) A component according to claim 18, wherein said metal carrier substrate is comprised of at least one metal selected from the group consisting of: aluminum, tin, copper, chromium, nickel, stainless steel and plated carbon steel.
- 28. (original) A component according to claim 27, wherein said separation facilitating layer is a comprised of a natural occurring oxide of at least one metal comprising said carrier substrate.
- 29. **(original)** A component according to claim 18, wherein said separation facilitating layer is a stabilization layer.
- 30. (currently amended) A component according to claim [[1]] 18, wherein said vapor-deposited layer of copper is formed by one of physical vapor deposition, chemical vapor deposition and a combination thereof.
- 31. (currently amended) A component according to claim [[30]] 18, wherein said vapor deposition includes vacuum deposition -deposited layer of copper is formed by sputtering.

- 32. (currently canceled)
- 33. (currently canceled)
- 34. (original) A component according to claim 18, wherein said carrier substrate has a weight per unit area in a range of 0.5 oz/ft² to 3 oz/ft².
- 35. (currently amended) A component according to claim [[1]] 18, wherein said vapor-deposited layer of copper is formed by a combustion chemical vapor deposition process.
- 36. (new) A component for use in forming a printed wiring board, comprising:

 a copper substrate;

 an inorganic separation facilitating layer formed on the copper substrate;

 a vapor-deposited layer of copper on the separation facilitating layer, wherein the vapor-deposited layer protects the separation facilitating layer; and

 an electrodeposited layer of copper on the vapor-deposited layer.
- 37. **(new)** A component according to claim 36, wherein said inorganic separation facilitating layer includes at least one metal oxide.
- 38. (new) A component according to claim 37, wherein said metal oxide is selected from the group consisting of: tin oxide, chromium oxide, nickel oxide, copper oxide, an oxide of stainless steel and zinc oxide.
- 39. (new) A component according to claim 38, wherein said inorganic separation facilitating layer has a thickness in a range of 5 Å to 1,000 Å.
- 40. (new) A component according to claim 39, wherein said stabilization layer includes chromium oxide and zinc oxide.

- 41. (new) A component according to claim 38, wherein said electrodeposited layer of copper has a thickness in a range of 1 μ m to 35 μ m.
- 42. (new) A component according to claim 38, wherein said carrier substrate has a weight per unit area in a range of 0.5 oz/ft² to 3 oz/ft².
 - 43. (new) A component for use in forming a printed wiring board, comprising: a metal carrier substrate;
- a separation facilitating layer formed of a metallic oxide on the metal carrier substrate, said separation facilitating layer having a thickness in a range of 5 Å to 1,000 Å;
- a vapor-deposited layer of copper on the separation facilitating layer, wherein the vapor-deposited layer protects the separation facilitating layer; and

an electrodeposited layer of copper on the vapor-deposited layer.

- 44. (new) A component according to claim 43, wherein said metal oxide is selected from the group consisting of: tin oxide, chromium oxide, nickel oxide, copper oxide, an oxide of stainless steel and zinc oxide.
- 45. (new) A component according to claim 44, wherein said carrier substrate is comprised of copper.
- 46. (new) A component according to claim 45, wherein said stabilization layer includes chromium oxide and zinc oxide.
- 47. (new) A component according to claim 45, wherein said electrodeposited layer of copper has a thickness in a range of 1 μ m to 35 μ m.

48. (new) A component according to claim 45, wherein said carrier substrate has a weight per unit area in a range of 0.5 oz/ft² to 3 oz/ft².